| Electronic Pate | ent App | lication Fee | Transm | ittal | | | |
|--|----------|--|----------|--------|-------------------------|--|--|
| Application Number: | 105 | 10571267 | | | | | |
| Filing Date: | 12- | 12-Feb-2007 | | | | | |
| Title of Invention: | | LITHOGRAPHY LENS SYSTEM AND PROJECTION EXPOSURE SYSTEM PROVIDED WITH AT LEAST ONE LITHOGRAPHY LENS SYSTEM OF THIS TYPE | | | | | |
| First Named Inventor/Applicant Name: | Ha | Hans-Juergen Rostalski | | | | | |
| Filer: | Kel | Kelly G. Hyndman/Mussie Beyene | | | | | |
| Attorney Docket Number: | Q9 | Q93721 | | | | | |
| Filed as Large Entity | <u>'</u> | | | | | | |
| U.S. National Stage under 35 USC 371 Fil | ling Fee | s | | | | | |
| Description | | Fee Code | Quantity | Amount | Sub-Total in USD(\$) | | |
| Basic Filing: | | | | | | | |
| Pages: | | | | | | | |
| Claims: | | | | | | | |
| Miscellaneous-Filing: | | | | | | | |
| Petition: | | | | | | | |
| Patent-Appeals-and-Interference: | | | | | | | |
| Post-Allowance-and-Post-Issuance: | | | | | | | |
| Utility Appl issue fee | | 1501 | 1 | 1510 | 1510 | | |
| | | | | | | | |

| Description | Fee Code | Quantity | Amount | Sub-Total in USD(\$) |
|--------------------|-------------------|----------|--------|-------------------------|
| Extension-of-Time: | | | | |
| Miscellaneous: | | | | |
| | Total in USD (\$) | | | 1810 |